

Recent Progress of the UVSOR-FEL

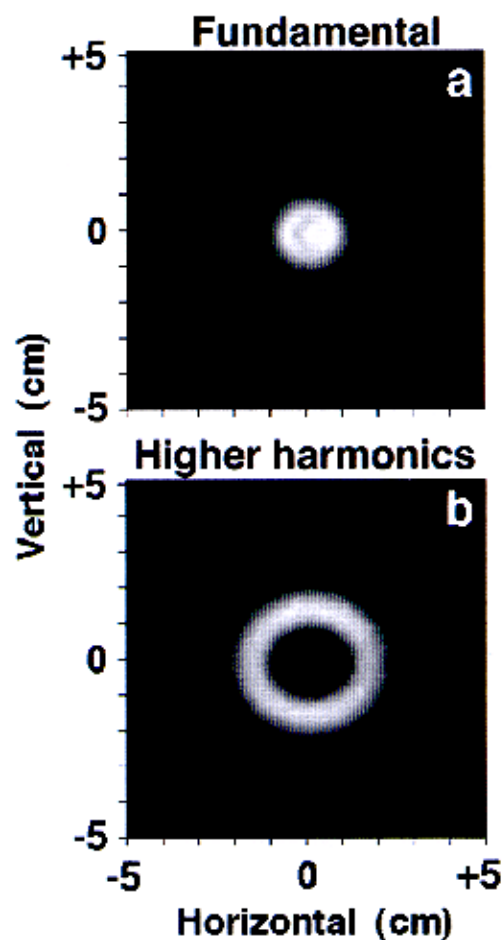
Hiroyuki Hama

with UVSOR Machine & FEL Group
(Masahito Hosaka, Shigeru Kouda, Jun-Ichiro Yamazaki)

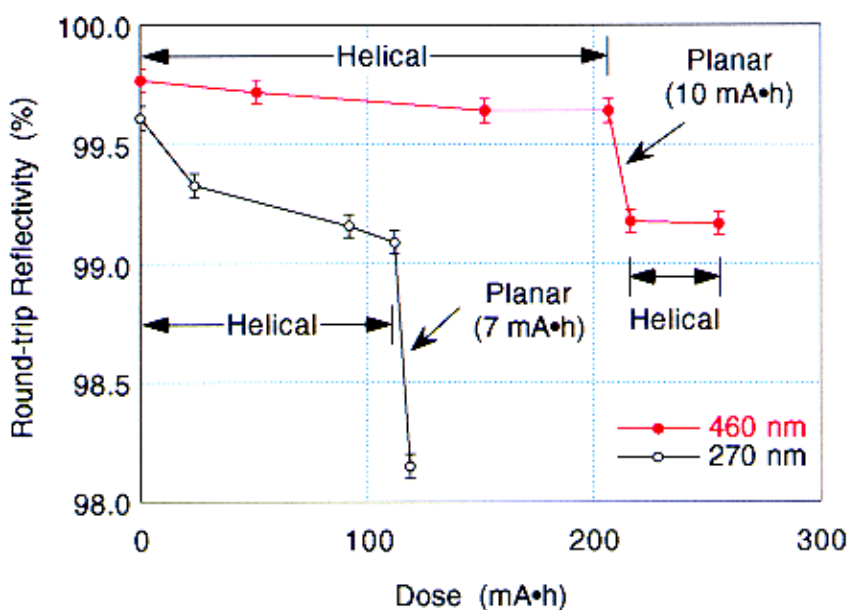
UVSOR Facility, Institute for Molecular Science, Myodaiji, Okazaki 444 Japan

Demonstration for mirror degradation with a helical optical klystron (UNSOR-FEL)

$\leq$ Calculated spatial intensity distribution (UNKO-3@600 MeV)



Mirror degradation rate (600 MeV)



Minon

Dielectric multilayers for high reflectance mirror

Quarter-wave multilayer with High-index and Low-index material

Low-index : SiO_2 transparent down to ~160 nm

High-index: Ta_2O_3 Super-ACO at 350 nm
 HfO_2 UVSOR at 240 nm
 Duke at 240 nm
 Al_2O_3 NIJI-IV at 210 nm

High-index material Absorption band (nm)

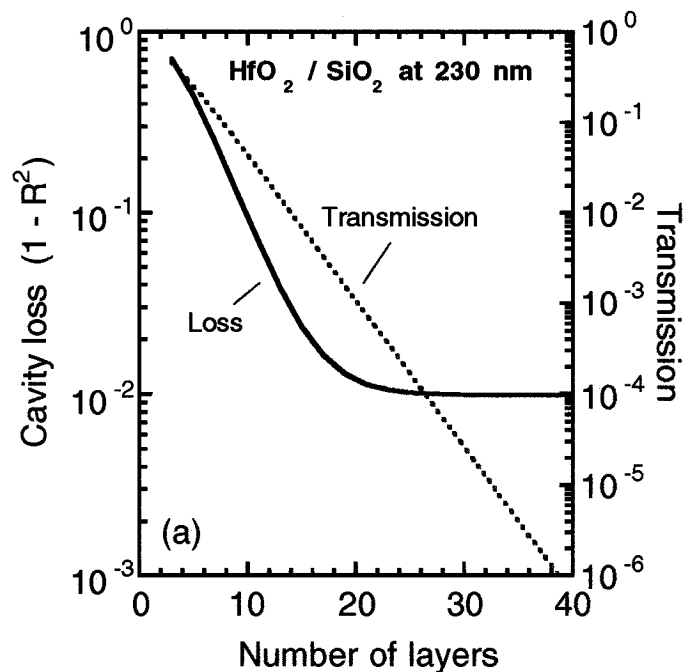
Ta_2O_3 ~ 300
 HfO_2 ~ 220
 Al_2O_3 ~ 170

Koppelman limit for maximum reflectance

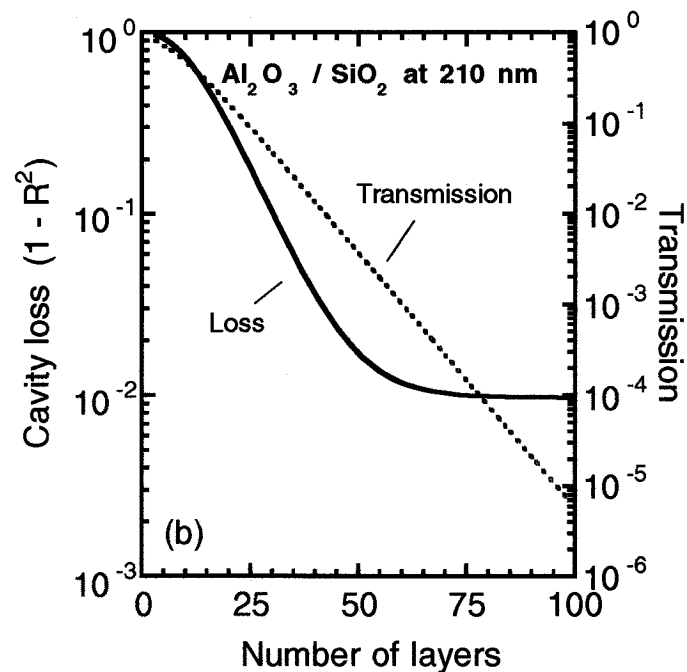
$$R_{\max} = 1 - 2\pi \frac{k_H + k_L}{n_H^2 + n_L^2} \quad n - ik ; \text{ optical constants} \quad n ; \text{ reflective} \quad k ; \text{ extinction}$$

Calculated reflectance and transmission with perfect polishing of substrate and layer coating

$\text{HfO}_2 / \text{SiO}_2$



$\text{Al}_2\text{O}_3 / \text{SiO}_2$



Maximum reflectance (Koppelman limit)

Multilayer	wavelength [nm]	max. R	saturated N	Transmission
<i>HfO₂ / SiO₂</i>	230	~ 99.5 %	> 31	< 0.000018
<i>Al₂O₃ / SiO₂</i>	210	~ 99.5 %	> 93	< 0.000014

Transmission rate may steeply decrease with the number of layers

If one wish transmission > 1 %,

<i>HfO₂ / SiO₂</i>	13 layers R = 98.1 %	T = 1.45 %
<i>Al₂O₃ / SiO₂</i>	41 layers R = 98.3 %	T = 1.18 %

Cavity loss => $1 - R^2$ 4 % loss for both cases => gain should be > 4 % !!!

Outcoupled power => $P_{out} = \text{mirror transmission} \times P$

To obtain the highest extraction efficiency, the BEST fabrication technique is required !

Optical Cavity Stability

Detuning range vs Macrotemporal structure (UVSOR-FEL)

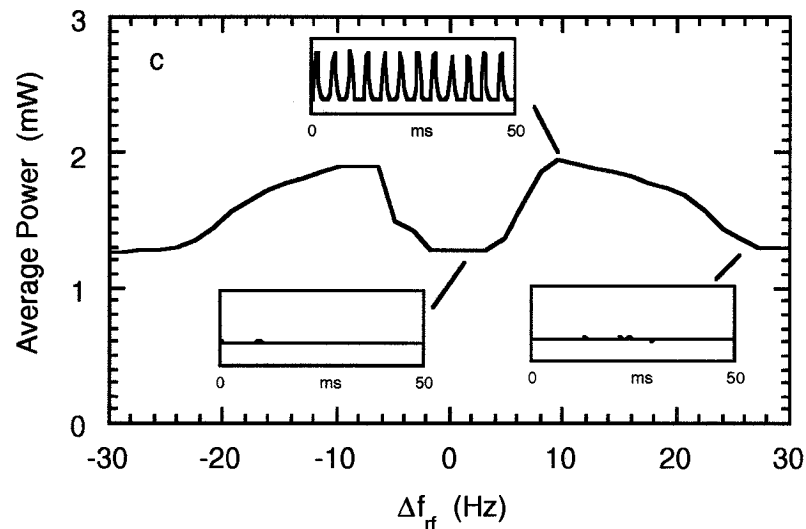
Zone	CW	Macropulse	Quasi-CW
$ \Delta f_{rf} $	$< 4 \text{ Hz}$	$< 25 \text{ Hz}$	$< 200 \text{ Hz}$
$ \Delta f_{rf} / f_{rf} $	$< 4 \times 10^{-8}$	$< 3 \times 10^{-7}$	$< 2 \times 10^{-6}$

$\frac{\Delta f_{RF}}{f_{RF}} \leq 10^{-8}$ to keep the highest saturation level.

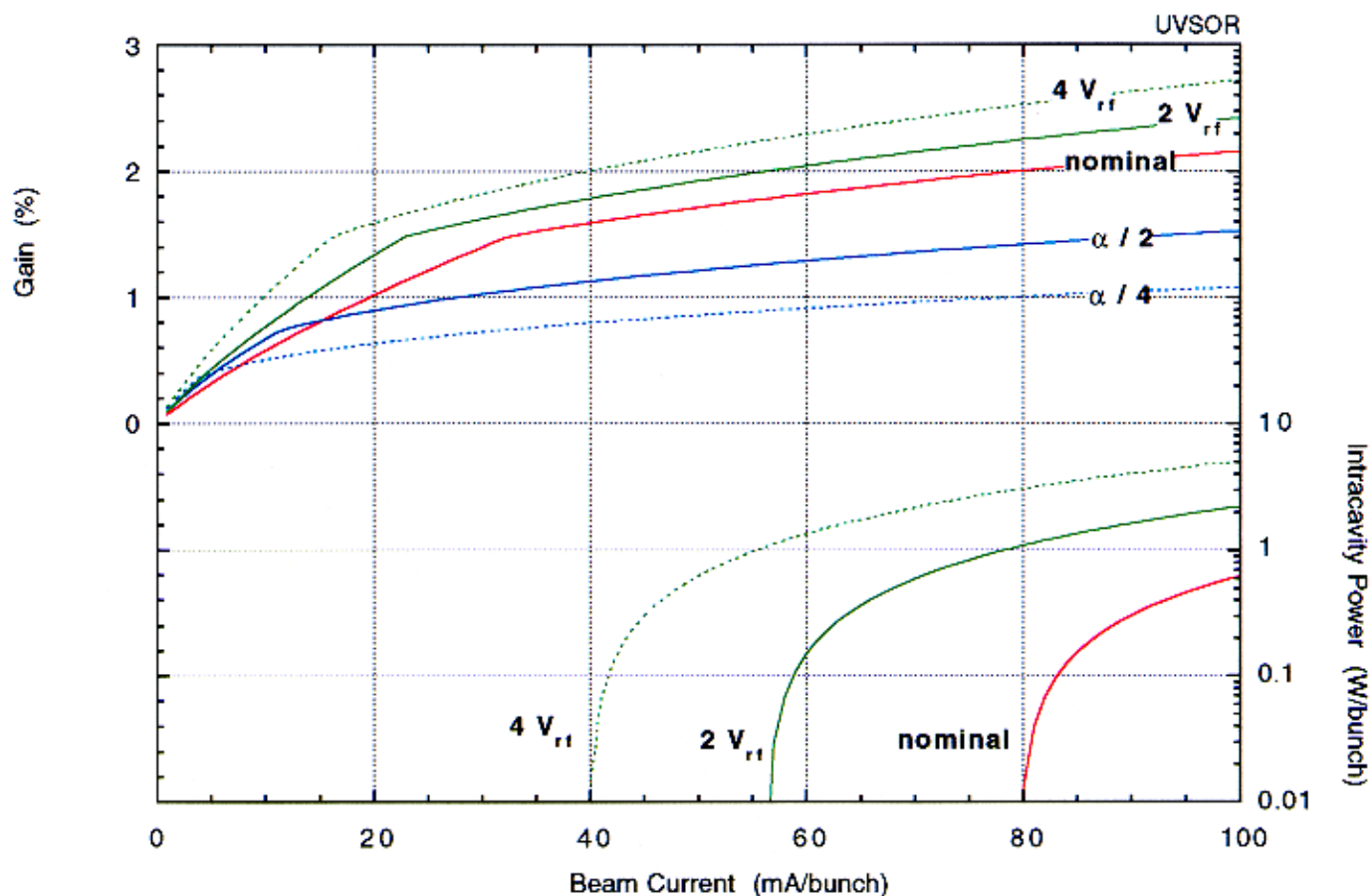
Cavity length $\Rightarrow \frac{\Delta L_{cavity}}{L_{cavity}} \leq 0.5 \mu m$

- i) Beam bunch jitter (usually very small $< 10 \text{ ps}$)
- ii) Mechanical vibration of mirror mount
- iii) Deformation of environment due to heat-up

Feedback system is absolutely necessary !!!!



Estimated Gain and Intracavity Power



Future Prospect of the UVSOR-FEL

- | | | |
|-----|---|--|
| [1] | Beam energy | 600 MeV => 750 MeV
high power
long lifetime
2-color experiment with FEL and SR |
| [2] | Ring impedance | 0.7 Ω => 0.2 ~ 0.3 Ω
Replace the beam pipes |
| [3] | Mirrors | T = 0.005 % => T = 0.1 %
Optimization of number of layers
~ 100 mW outcoupled power
HfO ₂ / SiO ₂ => Al ₂ O ₃ / SiO ₂
below 240 nm lasing |
| [4] | Optical cavity
(new one is under construction) | Heavy and solid base (marble stone, ~ 2 t)
Longitudinal feedback using a photon sampling oscilloscope
Good thermal contact for mirror holder |